REFERENCES

1. Ahmad S., Sadiq M., Hussain S., Shafiq M., Lee P., Zakaullah M. and Waheed A. (2006), Enhanced and Reproducible X-ray Emission in a Low-Energy Plasma Focus, *Europhys. Lett.*, **73 (1)**, pp. 42-48.
2. Ahmad S., Sadiq M., Hussain S., Shafiq M., Waheed A., Lee P. and Zakaullah M. (2006), The Effect of Pre-Ionization by a Shunt Resistor on the Reproducibility of Plasma Focus X-ray Emission, *Plasma Sources Sci. Technol.*, **15 (3)**, pp. 314-321.
3. Ahmad S., Shafiq M., Zakaullah M. and Waheed A. (2006), Depleted Uranium ($_{92}U^{238}$) Induced Preionization for Enhanced and Reproducible X-ray Emission from Plasma Focus, *Applied Physics Letters*, **89 (6)**, 061503.
4. Al-Hawat S. (2004), Axial Velocity Measurement of Current Sheath in a Plasma Focus Device using a Magnetic Probe. *IEEE Trans. Plasma Sci.*, **32 (2)**, pp. 764-769.
5. Aliaga-Rossel R. and Choi P. (1998), Experimental Observations of the Spatial Anisotropy of the Neutron Emission in a Medium Energy Plasma Focus, *IEEE Trans. Plasma Sci.*, **26 (4)**, pp. 1138-1145.
6. Asif M., and Ikram A. (2004), Electron Temperature Measurement using PIN Diodes as Detectors to Record the X-ray Pulses from a Low-energy Mather-type Plasma Focus, *Plasma Science & Technology*, **6 (2)**, pp. 2199-2203.
7. Banine V. and Moors R. (2004), Plasma Sources for EUV Lithography Exposure Tools, J. *Phys. D: Appl. Phys.*, **37**, pp. 3207-3212.
8. Bernstein M. J., Meskan D. A. and van Paassen H. L. L. (1969), Space, Time, and Energy Distributions of Neutrons and X-Rays from a Focused Plasma Discharge, *Phys. Fluids*, **12 (10)**, pp. 2193-2202.

9. Bernstein M. J. and Hai F. (1970), Evidence for Neutron production via Enhanced Resistivity in a Plasma Focus, *Phys. Rev. Letts.*, **25 (10)**, pp. 641-642.

10. Bernstein M. J., Lee C. M. and Hai F. (1971), Time Correlations of X-Ray Spectra with Neutron Emission from a Plasma Focus Discharge, *Phys. Rev. Letts.*, **27 (13)**, pp. 844-847.

11. Bhuyan H., Mohanty S. R., Neog N. K., Bujarbarua S. and Rout R. K. (2004), Comparative Study of Soft X-ray Emission Characteristics in a Low Energy Dense Plasma Focus Device, *Journal of Applied Physics*, **95 (6)**, pp. 2975-2981.

12. Bhuyan H., Chuaqui H., Favre M., Mitchell I. and Wyndham E. (2005), Ion Beam Emission in a Low Energy Plasma Focus device Operating with Methane, *J. Phys. D: Appl. Phys.*, **38 (8)**, pp. 1164-1169.

13. Bhuyan H., Favre M., Valderrama E., Chuanqui H. and Wyndham E. (2006), Experimental Studies of Ion Beam Anisotropy in a Low Energy Plasma Focus Operating with Methane, *J. Phys. D: Appl. Phys.*, **39 (16)**, pp. 3596-3602.

14. Böwering N., Martins M., Partlo W. N. and Fomenkov I. V. (2004), Extreme Ultraviolet Emission Spectra of Highly Ionized Xenon and Their Comparison with Model Calculations, *Journal of Applied Physics*, **95 (1)**, pp. 16-23.

15. Bogolyubov E. P., Bochkov V. D., Veretennikov V. A., Vekhoreva L. T., Gribkov V. A. Dubrovskii A. V., Ivanov Yu. P., Isakov A. I., Krokhin O. N., Lee P., Lee S., Nikulin V. Ya., Serban A., Silin P. V., Feng X. and Zhang G. X. (1998), A Powerful Soft X-Ray Source for X-Ray Lithography Based on Plasma Focusing, *Physica Scripta*, **57 (4)**, pp. 488-494.

16. Bostick W. H., Kilic H., Nardi V. and Powell C. W. (1993), Time Resolved Energy Spectrum of the Axial Ion Beam Generated in Plasma Focus Discharges, *Nuclear Fusion*, **33 (3)**, pp. 413-420.

17. Bruzzone H. and Vieytes R. (1993), The Initial Phase in Plasma Focus Device, *Plasma Physics and Controlled Fusion*, **35 (12)**, pp. 1745-1754.

18. Castillo F., Milanese M., Moroso R. and Pouzo J. (2000), Evidence of Thermal and Non-thermal Mechanisms Coexisting in Dense Plasma Focus D-D Nuclear Reactions, *Journal of Physics D-Applied Physics*, **33(2)**, pp. 141-147.

19. Castillo F., Milanese M. M., Moroso R. L., Pouzo J. O. and Santigo M. A. (2001), Small Plasma Focus Studies as a Source of Hard X-ray, *IEEE Trans. on Plasma Science*, **29 (6)**, pp. 921-926.

20. Deutsch R., Grauf W., Herold H. and Schmidt H. (1983), Self-organization Phenomena in the Plasma Focus, *Plasma Physics*, **25 (8)**, pp. 833-840.

21. Deutsch R. and Kies W. (1988), Manifestation of an Ion Acceleration Mechanism in Computer Simulations and Plasma-Focus Experiments, *Plasma Physics and Controlled Fusion*, **30 (8)**, pp. 921-934.

22. Donges A., Herziger G., Krompholz H., Rühl F. and Schönbach K. (1980), The Breakdown Phase in a Coaxial Plasma Gun, *Physics Letters*, **76A (5,6)**, pp. 391-392.

23. Favre M., Lee S., Moo S. P., and Wong C. S. (1992), X-ray Emission in a Small Plasma Focus Operating with H_2-Ar Mixtures, *Plasma Sources Sci. Technol.*, **1**, pp. 122-125.

24. Filippov N. V., Filippova T. I. and Vinogradov V. P. (1962), Dense, High-Temperature Plasma in a Noncylindrical 2-Pinch Compression, *Nuclear Fussion Suppl.*, **2**, pp. 577.

25. Filippov N. V. and Filippova T. I, (1965). *Proc 2nd Int. Conf. on Plasma Physics and Controlled Nuclear Fusion Research*, Culham, UK, pp. 270.

26. Fomenkov I., Partlo W. and Birx D. (1999), Characterization of a 13.5 nm Source for EUV lithography based on a Dense Plasma Focus and Lithium Emission, *Sematech International Workshop on Extreme Ultraviolet lithography*.

27. Fomenkov I. V., Partlo W. N., Ness R. M., Oliver I. R., Melnychuk S. T. ,Khodykin O. V. and Böwering N. R. (2002), Optimization of a Dense Plasma Focus Device as a Light Source for EUV Lithography, *SPIE Proc. on Emerging Lithographic Technologies VI*, **4688**, pp. 634-647.

28. Fomenkov I. V., Ness R. M., Oliver I. R., Melnychuk S. T., Khodykin O. V., Böwering N. R., Rettig C. L. and Hoffman J. R. (2003), Performance and Scaling of a Dense Plasma Focus Light Source for EUV Lithography, *SPIE Proc. on Emerging Lithographic Technologies VII*, **5037**, pp. 807-821.

29. Fomenkov I. V., Böwering N. R., Rettig C. L., Melnychuk S. T., Oliver I. R., Hoffman J. R., Khodykin O. V., Ness R. M. and Partlo W. N. (2004), EUV discharge Light Source based on a Dense Plasma Focus Operated with Positive and Negative Polarity, *J. Phys. D: Appl. Phys.*, **37 (23)**, pp. 3266-3276.

30. Fomenkov I. V., Ness R. M., Oliver I. R., Melnychuk S. T., Khodykin O. V., Böwering N. R., Rettig C. L. and Hoffman J. R. (2004), Performance and Scaling of a Dense Plasma Focus Light Source for EUV Lithography, *SPIE Proc. on Emerging Lithographic Technologies VIII*, **5374**, pp. 168-182.

31. Forrest M. J., and Peacock N. J. (1974), Measurement of Ion Temperature in Dense Plasma Focus by Laser-beam Scattering, *Plasma Physics and Controlled Fusion*, **16 (6)**, pp. 489-498.

32. Gribkov V. A., Srivastava A., Paul L., Kudryashov V. and Lee S. (2002), Operation of NX2 dense Plasma Focus Device with Argon Filling as a Possible Radiation Source for Micro-Machining, *IEEE Trans. on Plasma Science*, **30 (3)**, pp. 1331-1338.

33. Gupta R., Mohanty S. R., Rawat R. S. and Srivastava M. P. (2000), Current Sheath Dynamics and X-ray Emission Studies from Sequential Dense Plasma Focus Device, *IEEE Trans. on Plasma Science*, **28 (4)**, pp. 1263-1270.

34. Habibi M. and Amrollahi R. (2010), Anisotropic Investigation of Hard X-ray Emission with Flat Anode Tips in APF Plasma Focus Device, *J. Fusion Energy*, **29 (2)**, pp. 119-123.

35. Harries W. L., Lee J. H. and McFarland D. R. (1978), Trajectories of High Energy Electrons in a Plasma Focus, *Plasma Physics*, **20 (2)**, pp. 95-106.

36. Harries W. L., Lee J. H. and McFarland D. R. (1978), Space and Time Resolved Emission of Hard X-rays from a Plasma Focus, *Plasma Physics*, **20 (9)**, pp. 963-969.

37. Hassan S. M., Zhang T., Patran A., Rawat R. S., Springham S. V., Tan T. L., Wong D., Wang W., Lee S., Gribkov V. A., Mohanty S. R. and Lee P. (2006), Pinching Evidences in a Miniature Plasma Focus with Fast Pseudospark Swith, *Plasma Sources Sci. Technol.*, **15 (4)**, pp. 614-619.

38. Heo H. and Park D. K. (2002), Measurement of Argon Ion Beam and X-ray Energies in a Plasma Focus Discharge, *Physica Scripta*, **65**, pp. 350-355.

39. Hohl F. and Gary S. P. (1977), Electron Kinematics in a Plasma Focus, *Physics Fluids*, **20 (4)**, pp. 683-687.

40. Hussain S., Ahmad S., Khan M. Z., Zakaullah M. and Waheed A. (2003), Plasma Focus as a High Intensity Flash X-ray Source for Biological Radiography, *Journal of Fusion Energy*, **22 (3)**, pp. 195-200.

41. Hussain S., Zakaullah M., Ali S., Bhatti S. H. and Waheed A. (2003), X-ray Enhancement from a Plasma Focus by Inserting Lead at the Anode Tip, *Physics Letters A*, **319 (1-2)**, pp. 181-187.

42. Hussain S., Ahmad S., Sharif M., Sadiq M., Waheed A. and Zakaullah M. (2006), Comparative Studies of X-ray Emission from a Plasma Focus with Different Metal inserts at the Anode Tip, *Physics Letters A*, **349**, pp. 236-244.

43. Int. Symposium on Extreme Ultraviolet Lithography, Sept - Oct, 2008, Lake Tahoe, California.

44. International Technology Roadmap for Semiconductors at http://www.itrs.net/Links/2009ITRS/2009Chapters_2009Tables/2009_Litho.pdf.

45. Kant C. R., Srivastava M. P. and Rawat R. S. (1997), Thin Carbon Film Deposition using Energetic Ions of a Dense Plasma Focus, *Physics Letters A*, **226 (3-4)**, pp. 212-216.

46. Kelly H., Lepone A., Márquez A., Lamas D. and Oviedo C (1996), Coating on Metallic Samples Produced by a Small Energy Plasma Focus, *Plasma Sources Sci. Technol.*, **5 (4)**, pp. 704-709.

47. Kelly H. and Márquez A. (1996), Ion-Beam and neutron Production in a Low-Energy Plasma Focus, *Plasma Physics and Controlled Fusion*, **38 (11)**, pp. 1931-1942.

48. Koshelev K. N., Krauz V. I., Reshetniak N. G., Salukvadze R. G., Sidelnikov Y. V. and Khautiev E. Y. (1988), The Formation of the Micropinch Structure in Plasma Focus by the Addition of Heavy Impurities, *J. Phys. D: Appl. Phys.*, **21 (12)**, pp. 1827-1829.

49. Krompholz H., Neff W., Rühl F., Schönbach K. and Herziger G. (1980), Formation of the Plasma Layer in a Plasma Focus Device, *Physics Letters*, **77A (4)**, pp. 246-248.

50. Kubes P., Paduch M., Pisarczyk T., Scholz M., Klir D., Kravarik J., Rezac K., Chodukowski T., Ivanova-Stanik I., Karpinski L., Zielinska E., Tomaszewski K., and Sadowski M. J. (2010), Transformation of the Pinched Column at a Period of the Neutron Production, *IEEE Trans. on Plasma Science*, **38 (4)**, pp. 672-679.

51. Kwek K. H., Tou T. Y. and Lee S. (1990), Current Sheath Structures of the Plasma Focus in the Run-Down Phase, *IEEE Trans. on Plasma Science*, **18 (5)**, pp. 826-830.

52. Lee J. H., Loebbaka D. S. and Roos C. E. (1971), Hard X-ray Spectrum of a Plasma Focus, *Plasma Physics*, **13 (4)**, pp. 347-349.

53. Lee. S., Chen Y. H., Chow S. P., Tan B. C., Teh H. H. and Thong S. P. (1972), High-Speed Photography of a Plasma Focus, *Int. J. Electronics*, **33 (1)**, pp. 85-90.

54. Lee S., Tou T. Y., Moo S. P., Eissa M. A., Gholap A. V., Kwek K. H., Mulyodrono S., Smith A. J., Suryadi, Usada W. and Zakaullah M. (1988), A Simple Facility for the Teaching of Plasma Dynamics and Plasma Nuclear Fusion, *Am. J. Phys*, **56 (1)**, pp. 62-68.

55. Lee S., Alabraba M. A., Gholap A. V., Kumar S., Kwek K. H., Nisar M., Rawat R. S. and Singh J. (1990), Effect of Targets on Plasma Focus Dynamics, *IEEE Trans. on Plasma Science*, **18 (6)**, pp. 1028-1032.

56. Lee S. (1991), A Sequential Plasma Focus, *IEEE Trans. on Plasma Science*, **19 (5)**, pp. 912-919.

57. Lee S. and Serban A. (1996), Dimensions and Lifetime of the Plasma Focus Pinch, *IEEE Trans. on Plasma Science*, **24 (3)**, pp. 1101-1105.

58. Lee S., Lee P., Zhang G. X., Feng X., Gribkov V. A., Liu M. H. and Serban A.(1998), High Rep Rate High Performance Plasma Focus as a Powerful Radiation Source, *IEEE Trans. on Plasma Science*, **26 (4)**, pp. 1119-1126.

59. Lee S. (2009), Neutron Yield Saturation in Plasma Focus: A Fundamental Cause, *Applied Physics Letters*, **95 (15)**, 151503.

60. Lee S., Saw S. H., Lee P. and Rawat R. S. (2009), Numerical Experiments on Plasma Focus Neon Soft X-ray Scaling, *Plasma Phys. Control. Fusion*, **51 (10)**, 105013.

61. Liu M. H., Feng X., Springham S. V. and Lee S. (1998), Soft X-ray Yield measurement in a Small Plasma Focus Operated in Neon, *IEEE Trans. on Plasma Science*, **26 (2)**, pp. 135-140.

62. Lue J. T., Yeh C. K. and Kuo Y. Y. (1983), Annealing of Ion-Implanted Silicon by a Dense Plasma Focus, *IEEE Electron Device Letters*, **4 (12)**, pp. 457-459.

63. Mather J. W. (1964), Investigated of the High-Energy Acceleration Mode in the Coaxial Gun, *Physics Fluids Supplement*, **7**, pp. S28-S34.

64. Mather J. W. (1965), Formation of a High-Density Deuterium Plasma Focus, *Physics Fluids*, **8 (2)**, pp. 366-377.

65. Milanese M., Moroso R. and Pouzo J. (2003), D-D Neutron Yield in the 125 J Dense Plasma Focus Nanofocus, *Eur. Phys. J. D.*, **27 (1)**, pp. 77-81.

66. Mohammadi M. A., Verma R., Sobhanian S., Wong C. S., Lee S., Springham S. V., Tan T. L., Lee P. and Rawat R. S. (2007), Neon Soft X-ray Emission Studies from the UNU-ICTP Plasma Focus Operated with Longer Than Optimal Anode Length, Plasma *Sources Sci. Technol.*, **16 (4)**, pp. 785-790.

67. Mohanty S. R., Sakamoto T., Kobayashi Y., Song I., Watanabe M., Kawamura T., Okino A., Horioka K. and Hotta E. (2006), Miniature Hybrid Plasma Focus Extreme Ultraviolet Source Driven by 10 kA Fast Current Pulse, *Rev. Sci. Instrum.*, **77**, 043506.

68. Moo S. P., Chakrabarty C. K. and Lee S. (1991), An Investigated of the Ion Beam of a Plasma Focus Using a Metal Obstacle and Deuterated Target, *IEEE Trans. on Plasma Science*, **19 (3)**, pp. 515-519.

69. Moo S. P. and Wong C. S. (1995), Time Resolved Hard X-ray Emission from a Small Plasma Focus, *Laser and Particle Beams*, **13(1)**, pp. 129-134.

70. Moreno J., Silva P. and Soto L. (2003), Optical Observations of the Plasma Motion in a Fast Plasma Focus Operating at 50 J, *Plasma Sources Sci. Technol.*, **12 (1)**, pp. 39-45.

71. Nahrath B. (1978), *IPF-Report*-**78-1**, Stuttgart, FRG.

72. Nisar M., Khattak F. Y., Murtaza G., Zakaullah M. and Rashid N. (1993), Sequential Focusing in a Mather-Type Plasma Focus, *Physica Scripta.*, **47 (6)**, pp. 814-816.

73. Ng C. M., Moo S. P. and Wong C. S. (1998), Variation of Soft X-ray Emission with Gas Pressure in a Plasma Focus, *IEEE Trans. on Plasma Science*, **26 (4)**, pp. 1146-1153.

74. Partlo W., Fomenkov I. and Birx D. (1999), EUV (13.5 nm) Light Generation using a Dense Plasma Focus Device, *SPIE Proc. on Emerging Lithographic Technologies III*, **3676**, pp. 846-858.

75. Partlo W. N., Fomenkov I. V., Ness R. M., Oliver I. R., Melnychuk S. T. and Rauch J. E. (2001), Progress Toward Use of a Dense Plasma Focus as a Light Source for Production EUV Lithography, *SPIE Proc. on Emerging Lithographic Technologies V*, **4343**, pp. 232-248

76. Pavez C. and Soto L. (2010), Demostration of X-ray Emission from an Ultraminiature Pinch Plasma Focus Discharge Operating at 0.1 J Nanofocus, *IEEE Trans. on Plasma Science*, **38 (5)**, pp. 1132-1135.

77. Raspa V., Moreno C., Sigaut L. and Clausse A. (2007)., Effective Hard X-ray Spectrum of a Tabletop Mather-type Plasma Focus Optimized for Flash Radiography of Metallic Objects, *Journal of Applied Physics*, **102 (12)**, 123303.

78. Sánchez G., Grigioni G. and Feugeas J. (1995), Thermal Effect of Ion Implantation with Ultra-Short Ion Beams, *Surface and Coatings Technology*, **70**, pp. 181-186.

79. Sadowki M., Żebrowski J., Rydygier E. and Kuciński J. (1988), Ion Emission from Plasma Focus Facilities, *Plasma Physics and Controlled Fusion*, **30 (6)**, pp. 763-769.

80. Schmidt H., Kasperczuk A.. Paduch M., Pisarczyk T., Scholz M., Tomaszewski K. and Szydowski A. (2002), Review of Recent Experiments with the Megajoule PF-1000 Plasma Focus Device, *Physica Scripta*, **66 (2)**, pp. 168-172.

81. Schneider R. F., Rhee M. J. and Smith J. R. (1985), Experimental Study of the Electron Beam Produced by a Plasma Focus Accelerator, *IEEE Trans. on Nuclear Science*, **32 (5)**, pp. 3536-3538.

82. Serban A. and Lee S. (1997), Soft X-ray Emission from a Small Plasma Focus Operated in Deuterium, *Plasma Sources Sci. Technol.*, **6 (1)**, pp. 78-85.

83. Shafiq M., Hussain S., Sahrif M. and Zakaullah M. (2002), Soft X-ray Emission Optimization Study with Nitrogen Gas in a 1.2 kJ Plasma Focus, *Journal of Fusion Energy*, **20 (3)**, pp. 113-115.

84. Shafiq M., Hussain S., Waheed A., Zakaullah M. (2003), X-ray Emission From a Plasma Focus with High-Z inserts at the Anode Tip, *Plasma Source Sci. Technol.*, **12 (2)**, pp. 199-204.

85. Sharif M., Hussain S., Zakaullah M. and Waheed A. (2004), Study of the X-ray Emission Scaling Law in a Low Energy Plasma Focus, *Plasma Source Sci. Technol.*, **13 (4)**, pp. B7-B13.

86. Silva P., Soto L., Moreno J., Sylvester G., Zambra M., Altamirano L., Bruzzone H., Clausse A. and Moreno C. (2001), Characterization of a Very Small Plasma Focus in the Limit of Low Energy (50 J), *International Symposium SHAPES 2001*, Warsaw, Poland, Proc. CD Plasma 2001, pp. 3.8.

87. Silva P., and Favre M. (2002), Properties of Hotspots in Plasma Focus Discharges Operating in Hydrogen-argon Mixtures, *Journal of Physics D: Applied Physics*, **35 (20)**, pp. 2543-2550.

88. Silva P., Moreno J., Soto L., Birstein L., Mayer E. and Kies W. (2003), Neutron Emission from a Fast Plasma Focus of 400 Joules, *Applied Physics Letters*, **83 (16)**, pp. 3269-3271.

89. Soto L., Silva P., Moreno J., Silvester G., Zambra M., Pavez C., Altamirano L., Bruzzone H., Barbaglia M., Sidelnikov Y. and Kies W. (2004), Research on Pinch Plasma Focus Devices of Hundred of Kilojoules to Tens of Joules, *Brazilian Journal of Physics*, **34 (4B)**, pp. 1814-1821.

90. Soto L. (2005), New Trends and Future Perspectives on Plasma Focus Research, *Plasma Phys. Control. Fusion*, **47**, A361–A381.

91. Soto L., Pavez C. Moreno J., Barbaglia M. and Clausse A. (2009), Nanofocus: An Ultra-Miniature Dense Pinch Plasma Focus Device with Submillimetric Anode Operating at 0.1 J, *Plasma Sources Sci. Technol.*, **18 (1)**, 015007.

92. Stamm U. (2004), Extreme Ultraviolet Light Sources for Use in Semiconductor Lithography – State of the Art and Future Development, *J. Phys. D: Appl. Phys.*, **37 (23)**, pp. 3244-3253.

93. Takao K., Honda T., Kitamura I. and Masugata K. (2003), Purity of Nitrogen Ion Beams Produced in a Plasma Focus, *Plasma Sources Sci. Technol.*, **12 (3)**, pp. 407-411.

94. Tangjitsomboon P., Ngamrungroj D., Wong C. S. and Mongkolnavin R. (2009), Operating Parameters for Extreme Ultraviolet Radiation Generation based on the United Nations University/ International Centre for theoretical Physics (UNU/ICTP) Plasma Focus Device, *Journal of Science and Technology in the Tropics*, **5**, pp. 39-43.

95. Verma R., Lee P., Lee S., Springham S. V., Tan T. L., Rawat R. S. and Krishnan M. (2008), Order of Magnitude Enhancement in Neutron Emission with Deuterium-Krypton Admixture Operation in Miniature Plasma Focus Device, *Applied Physics Letters*, **93 (10)**, 101501.

96. Verma R., Lee P., Springham S. V., Tan T. L., Rawat R. S. and Krishnan M. (2008), Order of Magnitude Enhancement in X-ray Yield at Low Pressure Deuterium-Krypton Admixture Operation in Miniature Plasma Focus Device, *Applied Physics Letters*, **92 (1)**, 011506.

97. Verma R., Roshan M. V., Malik F., Lee P., Lee S., Springham S. V., Tan T. L., Krishnan M. and Rawat R. S. (2008), Compact Sub-kilojoule Range fast Miniature Plasma Focus as Portable Neutron Source, *Plasma Sources Sci. Technol.*, **17 (4)**, 045020.

98. Verma R., Rawat R. S., Lee P., Krishnan M., Springham S. V. and Tan T. L. (2010), Miniature Plasma Focus Device as a Compact Hard X-ray Source for Fast Radiography Applications, *IEEE Trans. on Plasma Science*, **38 (4)**, pp. 652-657.

99. Wang J. and Yang T. C. (1988), A Study of X-ray Emission from the Anode Region in a Plasma Focus Device, *J. Phys. D: Appl. Phys.*, **21 (5)**, pp. 700-709.

100. Wong D., Patran A., Tan T. L., Rawat R. S. and Lee P. (2004) Soft X-ray optimization Studies on a Dense Plasma Focus Device Operated in Neon and Argon in Repetitive Mode, *IEEE Trans. on Plasma Science*, **32 (6)**, pp. 2227-2235.

101. Wurm S. (2009), EUV Lithography Development and Research Challenges for the 22 nm Half-pitch, *Journal of Photopolymer Science and Technology*, **22 (1)**, pp. 31-42.

102. Yap S. L., Larour J., Choi P., Rous J., Dine S., Pavelescu G., Favre M., Guilbert A. and Wong C. S. (2002), Ion Beam Measurements of a Low Pressure Plasma Focus, *Jurnal Fizik Malaysia*, **23 (1&2)**, pp. 47-50.

103. Yap S. L. and Wong C. S., Choi P., Dumitrescu C. and Moo S. P. (2005), Observation of Two Phases of Neutron Emission in a Low Energy Plasma Focus, *Japanese Journal of Applied Physics*, **44(11)**, pp. 8125-8132.

104. Zakaullah M., Ahmad I., Omar A., Murtaza G. and Beg M. M. (1996), Effects of Anode Shape on Plasma Focus Operation with Argon, *Plasma Sources Sci. Technol.*, **5 (3)**, pp. 544-552.

105. Zakaullah M, Murtaza G., Qamar S., Ahmad I. and Beg M.M. (1996), Neutron and X-ray Emission Studies in a Low Energy Plasma Focus, *Physica Scripta*, **53 (3)**, pp. 360-363.

106. Zakaullah M., Alamgir K., Murtaza G. and Waheed A. (2000), Efficiency of Plasma Focus for Argon K-series Line Radiation Emission, *Plasma Sources Sci. Technol.*, **9 (4)**, pp. 592-596.

107. Zakaullah M., Alamgir K., Shafiq M., Hassan S. M. and Sharif M. (2001), Enhanced Copper K-alpha Radiation from a Low Energy Plasma Focus, *Applied Physics Letters*, **78 (7)**, pp. 877-879.